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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/720,122	11/25/2003	Toshio Tsujimoto	245926US0XDIV	4386
	7590 01/05/200 AK, MCCLELLAND 1	EXAMINER		
1940 DUKE STREET ALEXANDRIA, VA 22314			SONG, MATTHEW J	
ALEAANDRIA, VA 22314			ART UNIT	PAPER NUMBER
		1792		
			NOTIFICATION DATE	DELIVERY MODE
			01/05/2009	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

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Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)		
10/720,122	TSUJIMOTO ET AL.		
Examiner	Art Unit		

	MATTHEW J. SONG	1792	
The MAILING DATE of this communication appe	ars on the cover sheet with the o	correspondence add	ress
THE REPLY FILED 11 December 2008 FAILS TO PLACE THIS	APPLICATION IN CONDITION F	OR ALLOWANCE.	
 The reply was filed after a final rejection, but prior to or on application, applicant must timely file one of the following r application in condition for allowance; (2) a Notice of Appe for Continued Examination (RCE) in compliance with 37 C periods: 	eplies: (1) an amendment, affidavi al (with appeal fee) in compliance	t, or other evidence, w with 37 CFR 41.31; or	hich places the (3) a Request
a) \boxtimes The period for reply expires $\underline{5}$ months from the mailing date	of the final rejection.		
b) The period for reply expires on: (1) the mailing date of this Adno event, however, will the statutory period for reply expire la Examiner Note: If box 1 is checked, check either box (a) or (I MONTHS OF THE FINAL REJECTION. See MPEP 706.07(f	ter than SIX MONTHS from the mailing b). ONLY CHECK BOX (b) WHEN THE).	g date of the final rejectio FIRST REPLY WAS FIL	on. LED WITHIN TWO
Extensions of time may be obtained under 37 CFR 1.136(a). The date of have been filed is the date for purposes of determining the period of extra under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the size forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b). NOTICE OF APPEAL	ension and the corresponding amount nortened statutory period for reply origi	of the fee. The appropria nally set in the final Offic	ate extension fee e action; or (2) as
2. The Notice of Appeal was filed on A brief in compl filing the Notice of Appeal (37 CFR 41.37(a)), or any exten Notice of Appeal has been filed, any reply must be filed wi	sion thereof (37 CFR 41.37(e)), to	avoid dismissal of the	
AMENDMENTS	mais a to the state of filling a bais f		
3. The proposed amendment(s) filed after a final rejection, be (a) They raise new issues that would require further con (b) They raise the issue of new matter (see NOTE below (c) They are not deemed to place the application in bett	sideration and/or search (see NO ⁻ v);	ΓE below);	
appeal; and/or	er form for appear by materially rec	adding of Simplifying th	10 133403 101
(d) ☐ They present additional claims without canceling a c NOTE: <u>See Continuation Sheet</u> . (See 37 CFR 1.12		ected claims.	
4. The amendments are not in compliance with 37 CFR 1.12	* **	mpliant Amendment (F	PTOL-324).
5. Applicant's reply has overcome the following rejection(s):		(
6. Newly proposed or amended claim(s) would be allowed non-allowable claim(s).		timely filed amendmer	it canceling the
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is prove The status of the claim(s) is (or will be) as follows:		l be entered and an ex	cplanation of
Claim(s) allowed: Claim(s) objected to:			
Claim(s) rejected: <u>14-16,18,19,21,22,24 and 26</u> . Claim(s) withdrawn from consideration:			
<u>AFFIDAVIT OR OTHER EVIDENCE</u> 8.	hefore or on the date of filing a No	atice of Anneal will not	he entered
because applicant failed to provide a showing of good and was not earlier presented. See 37 CFR 1.116(e).			
 The affidavit or other evidence filed after the date of filing a entered because the affidavit or other evidence failed to or showing a good and sufficient reasons why it is necessary 	vercome <u>all</u> rejections under appea and was not earlier presented. Se	al and/or appellant fails see 37 CFR 41.33(d)(1)	s to provide a).
10. ☐ The affidavit or other evidence is entered. An explanation REQUEST FOR RECONSIDERATION/OTHER	of the status of the claims after e	ntry is below or attache	∍d.
 The request for reconsideration has been considered but <u>See Continuation Sheet.</u> 	does NOT place the application in	condition for allowand	ce because:
12. ☐ Note the attached Information <i>Disclosure Statement</i>(s). (13. ☐ Other:	PTO/SB/08) Paper No(s)		
/Michael Kornakov/ Supervisory Patent Examiner, Art Unit 1792	/Matthew Song/ Examiner		

Continuation of 3. NOTE: The amendment raises new issues as to the dependant claims because the combination of limitations was not considered previously, thus would require further search and consideration.

Continuation of 11. does NOT place the application in condition for allowance because: Applicant's arguments filed 12/11/2008 have been fully considered but they are not persuasive.

Applicant argument that there are advantages to the sol gel method which are not obtained by the process taught by Watanabe and Hansen is noted but not found persuasive. Applicant alleges that the uniformity of concentration is not taught by the prior art. The Examiner admits that the prior art does not explicitly teach the concentration is uniform however it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify the combination of Hansen and Watanabe to obtain a uniform concentration. Applicant also alleges that the silica sol strength is such that the promoter does not dissolve in the silicon melt. There is no support for this alleged feature in applicant's original disclosure. Applicant also alleges the formation of an uniform cristobalite layer. This argument is not persuasive because the claims do not require the formation of cristobalite layer and the formation of uniform cristobalite layer is expected since a uniformly dispersed crystallization promoter would have been obvious, as discussed previously.

Applicant's argument that the combination of Hansen and Watanabe produces microscopic nonuniformity and uniform, strong layer is not formed is noted but not found persuasive. This is mere attorney argument which lacks evidence; therefore is not found persuasive. Applicant merely alleges that the prior art produces microscopic nonuniformity without providing any evidence to support the argument. Also, the original disclosure merely discusses uniformity and does not teach that the instantly claimed method produces microscopic uniformity, thus the arguments are discussing features which are not supported by the original disclosure. Applicant's argument that there is no suggestion to prepare the crystallization promoter containing layer in a sol gel process is noted but not

Applicant's argument that there is no suggestion to prepare the crystallization promoter containing layer in a sol gel process is noted but no found persuasive. The patentability determination of a product-by-process claim is based on the patentability of the product and does not depend on its method of production (MPEP 2113). The product would have been obvious for the reason discussed in the rejection.

Applicant's argument that Watanabe and Hansen cannot be combined is noted but not found persuasive. Hansen teaches a crucible surface can be coated by any method that deposits a devitrification promoter to the surface (col 7, ln 35-45); therefore Hansen is not limited to any particular method of forming a promoter layer. Watanabe et al teaches a method of forming a promoter layer by dispersing a promoter in a silicon oxide powder such that the promoter can be fused to the base body (col 3, ln 25-40; col 4, ln 15-30 and col 5, ln 5-30). Watanabe et al is not relied upon as a teaching to improve the inner surface of a crucible. Watanabe et al is merely relied upon to teach an known method of forming a promoter layer. Watanabe et al's method of forming the promoter layer does not require forming the additional silicon layer.

In response to applicant's argument that the references fail to show certain features of applicant's invention, it is noted that the features upon which applicant relies (i.e., a thin layer less than 1 micrometer) are not recited in the rejected claim(s). Although the claims are interpreted in light of the specification, limitations from the specification are not read into the claims. See In re Van Geuns, 988 F.2d 1181, 26 USPQ2d 1057 (Fed. Cir. 1993).

Applicant's arguments regarding the declaration is noted but not found persuasive. The declaration is also outside the scope of the claimed invention because the declaration alleges unexpected results for thicknesses of the layers, however the claims do not recite any thickness limitation.